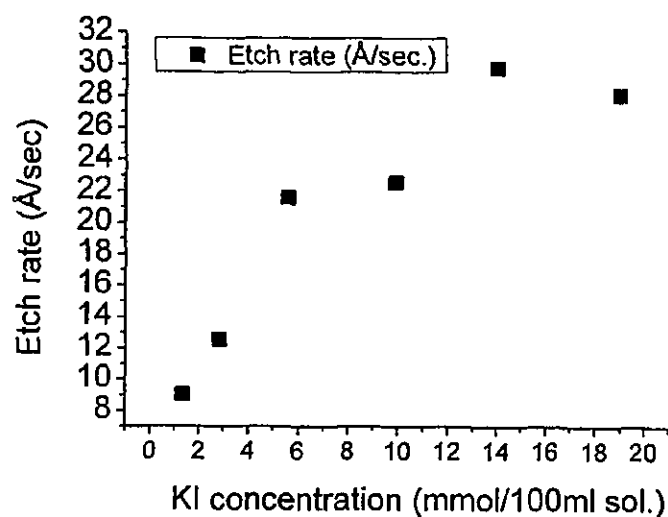
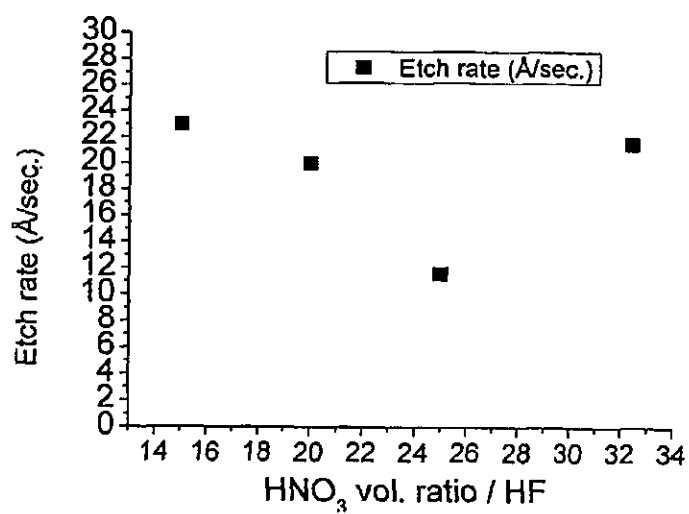


Figure 1



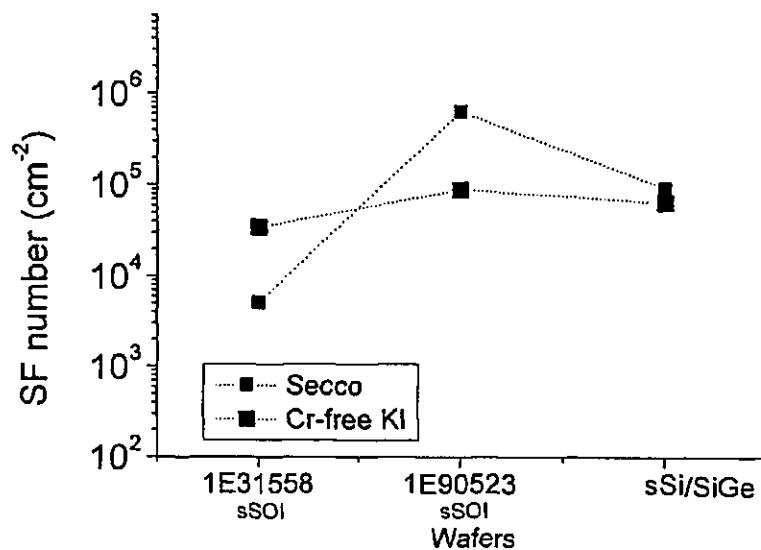
Etching rates as a function of KI concentration for a solution with volume ratios 1/32.4/34.

Figure 2



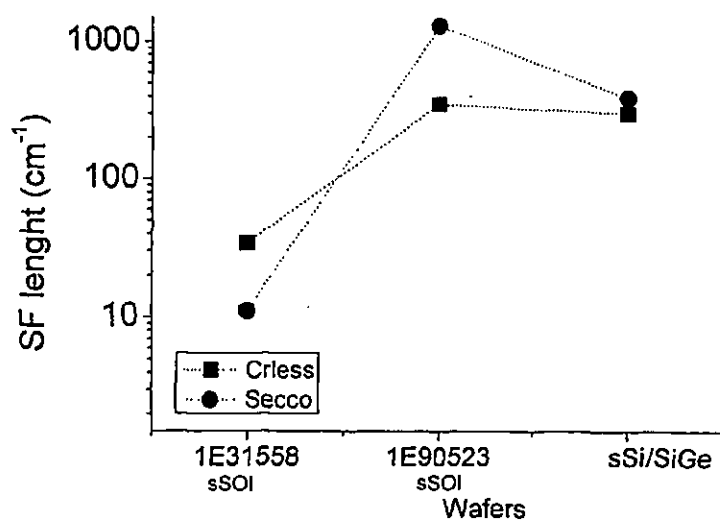
Etch rates as a function of HNO₃ volume ratio (/HF) for a solution HF/HNO₃/CH₃COOH + KI = 6 mmol à 100 ml sol.

Figure 3



SF number correlation between a Cr-free etch containing KI and Secco for sSOI and sSi/SiGe wafers.

Figure 4



SF length correlation between a Cr-free etch containing KI and Secco for various wafers